

## **AMENDMENTS TO THE SPECIFICATION**

Please replace current paragraph 22 with the paragraph below, having the indicated amendments:

[0022] Figure 8 shows a top view of the substrate structure shown in Figure 4 prior to ion-implanting the compression element in the PMOS region. The dotted line shows an interface between a device region 32 and the STI region 16 surrounding the device region 32. The second mask 22 covers not only the STI region 16 but also portions of the device region 32 except for a center portion 34 of the device region expected to be a channel region for a PMOS device to be formed.